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INFORMATION DISCLOSURE
STATEMENT BY APPLICANT

ATTORNEY'S DKT NO.
015290-546APPLICATION NO.
10/024,208APPLICANT
David J. Cooperberg et alFILING DATE
December 21, 2001GROUP
1763

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| Examiner Initials | U.S. Patent Document | | Name of Patentee or Applicant of Cited Document | Date of Publication (MM-DD-YYYY) |
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